

# (12) United States Patent

Masuda et al.

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### PLASMA PROCESSING APPARATUS AND (54)PLASMA PROCESSING METHOD

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### (30)Foreign Application Priority Data

•	` ′	
(51) Int. Cl.		 H01L 21/00

(52) **U.S. Cl.** ...... **438/715**; 156/345.44; 156/345.46; 156/345.48; 156/345.49; 216/68; 216/70; 438/729

**Field of Search** ...... 156/345 P, 345 C, 156/345 ME, 345 MG, 345 PH; 438/710, 715, 728, 729, 732; 216/67, 70, 71, 68

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#### (57)**ABSTRACT**

In a plasma processing apparatus that has a vacuum chamber, a process gas supply means of supply gas to a processing chamber, an electrode to hold a sample inside said vacuum chamber, a plasma generator installed in said vacuum chamber opposite to said sample, and a vacuum exhaust system to decrease pressure of said vacuum chamber, a bias voltage of Vdc=-300 to -50 V is applied and the surface temperature of said plate ranges from 100 to 200° C. In addition, the surface temperature fluctuation of the silicon-made plate in said plasma processing apparatus is kept within ±25° C.

### 10 Claims, 7 Drawing Sheets

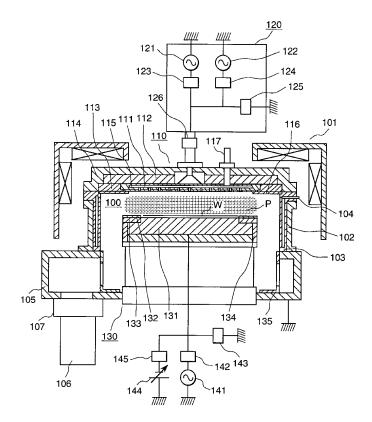




FIG. 1

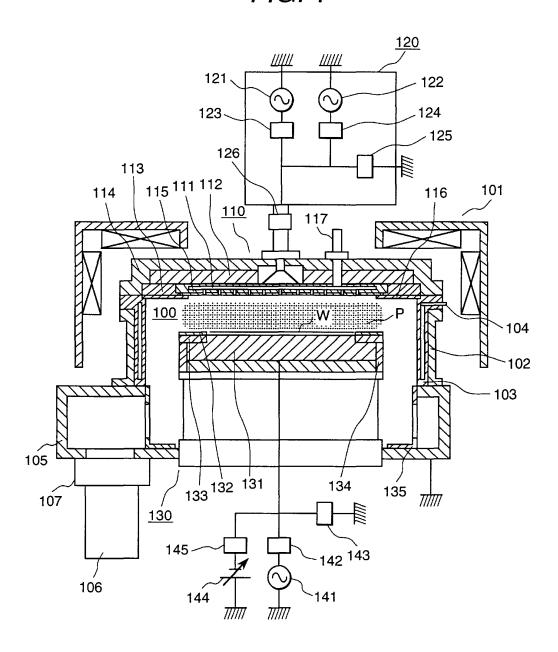


FIG. 2

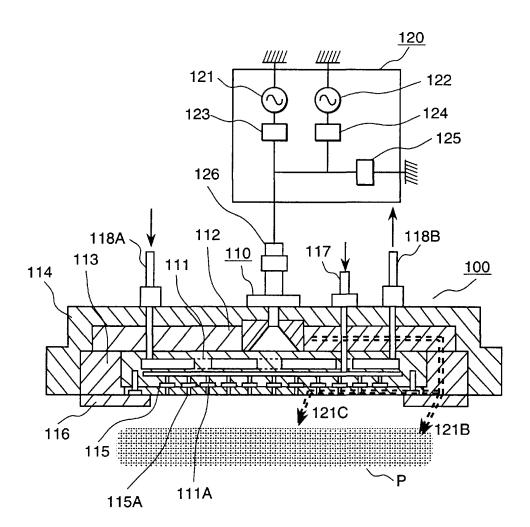


FIG. 3

Si ETCHING RATE (  $\mu$  m/h)

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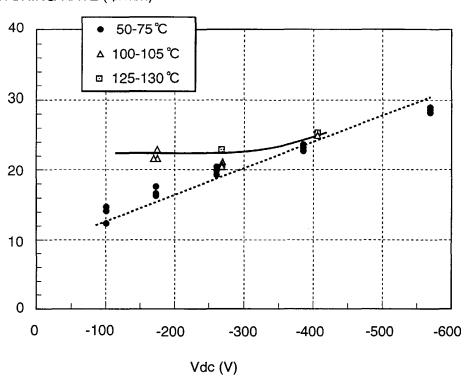


FIG. 4

TEMPERATURE (deg)

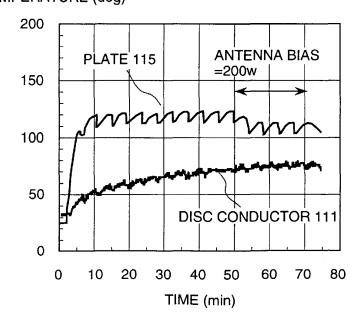


FIG. 5

TEMPERATURE (deg)

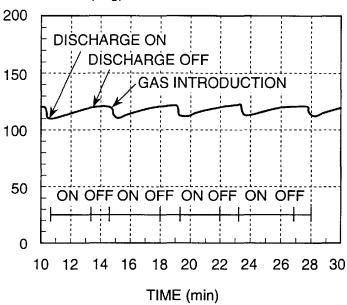
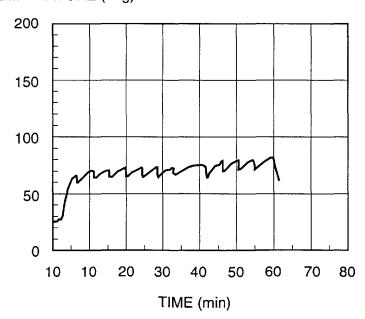


FIG. 6

TEMPERATURE (deg)





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